

Masaharu Shiratani

List of Publications by Year in descending order

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336
papers

5,522
citations

94433

37
h-index

138484

58
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342
all docs

342
docs citations

342
times ranked

3135
citing authors

#	ARTICLE	IF	CITATIONS
1	Biogenic reductive preparation of magnetic inverse spinel iron oxide nanoparticles for the adsorption removal of heavy metals. <i>Chemical Engineering Journal</i> , 2017, 307, 74-84.	12.7	226
2	Surface reaction probabilities and kinetics of H, SiH ₃ , Si ₂ H ₅ , CH ₃ , and C ₂ H ₅ during deposition of a-Si:H and a-C:H from H ₂ , SiH ₄ , and CH ₄ discharges. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1998, 16, 278-289.	2.1	219
3	Plasma agriculture: A rapidly emerging field. <i>Plasma Processes and Polymers</i> , 2018, 15, 1700174.	3.0	174
4	Current status and future prospects of agricultural applications using atmospheric pressure plasma technologies. <i>Plasma Processes and Polymers</i> , 2018, 15, 1700073.	3.0	156
5	Plasma Agriculture from Laboratory to Farm: A Review. <i>Processes</i> , 2020, 8, 1002.	2.8	125
6	Review of pulmonary toxicity of indium compounds to animals and humans. <i>Thin Solid Films</i> , 2010, 518, 2934-2936.	1.8	95
7	Simultaneous in situ measurements of properties of particulates in rf silane plasmas using a polarization sensitive laser light scattering method. <i>Journal of Applied Physics</i> , 1996, 79, 104-109.	2.5	94
8	Plasma induced long-term growth enhancement of <i>Raphanus sativus</i> L. using combinatorial atmospheric air dielectric barrier discharge plasmas. <i>Current Applied Physics</i> , 2014, 14, S149-S153.	2.4	85
9	Effects of Gas Temperature Gradient, Pulse Discharge Modulation, and Hydrogen Dilution on Particle Growth in Silane RF Discharges. <i>Japanese Journal of Applied Physics</i> , 2000, 39, 287-293.	1.5	84
10	Simple method of improving harvest by nonthermal air plasma irradiation of seeds of <i>Arabidopsis thaliana</i> (L.). <i>Applied Physics Express</i> , 2016, 9, 016201.	2.4	83
11	In situ observation of nucleation and subsequent growth of clusters in silane radio frequency discharges. <i>Applied Physics Letters</i> , 2000, 77, 196-198.	3.3	77
12	Growth processes of particles in high frequency silane plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1996, 14, 540-545.	2.1	71
13	Mechanism and comparison of needle-type non-thermal direct and indirect atmospheric pressure plasma jets on the degradation of dyes. <i>Scientific Reports</i> , 2016, 6, 34419.	3.3	71
14	Influence of ionic liquid and ionic salt on protein against the reactive species generated using dielectric barrier discharge plasma. <i>Scientific Reports</i> , 2015, 5, 17781.	3.3	70
15	Effects of plasma irradiation using various feeding gases on growth of <i>Raphanus sativus</i> L.. <i>Archives of Biochemistry and Biophysics</i> , 2016, 605, 129-140.	3.0	64
16	Particle Growth Kinetics in Silane RF Discharges. <i>Japanese Journal of Applied Physics</i> , 1999, 38, 4542-4549.	1.5	61
17	Highly Conducting and Very Thin ZnO:Al Films with ZnO Buffer Layer Fabricated by Solid Phase Crystallization from Amorphous Phase. <i>Applied Physics Express</i> , 2011, 4, 011101.	2.4	61
18	Growth Enhancement of Radish Sprouts Induced by Low Pressure O ₂ Radio Frequency Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AE01.	1.5	58

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19	Highly Stable a-Si:H Films Deposited by Using Multi-Hollow Plasma Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2005, 44, L1430-L1432.	1.5	57
20	Effects of nonthermal plasma jet irradiation on the selective production of H ₂ O ₂ and NO ₂ in liquid water. Journal of Applied Physics, 2016, 120, .	2.5	52
21	Contribution of short lifetime radicals to the growth of particles in SiH ₄ high frequency discharges and the effects of particles on deposited films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 995-1001.	2.1	50
22	Single step method to deposit Si quantum dot films using H ₂ +SiH ₄ VHF discharges and electron mobility in a Si quantum dot solar cell. Surface and Coatings Technology, 2007, 201, 5468-5471.	4.8	50
23	Impact of Gamma rays and DBD plasma treatments on wastewater treatment. Scientific Reports, 2018, 8, 2926.	3.3	49
24	Fabrication of Nanoparticle Composite Porous Films Having Ultralow Dielectric Constant. Japanese Journal of Applied Physics, 2005, 44, L1509-L1511.	1.5	48
25	Detection of particles in rf silane plasmas using photoemission method. Journal of Applied Physics, 1996, 80, 3202-3207.	2.5	47
26	Growth Control of Dry Yeast Using Scalable Atmospheric-Pressure Dielectric Barrier Discharge Plasma Irradiation. Japanese Journal of Applied Physics, 2012, 51, 11PJ02.	1.5	47
27	Cluster-Suppressed Plasma Chemical Vapor Deposition Method for High Quality Hydrogenated Amorphous Silicon Films. Japanese Journal of Applied Physics, 2002, 41, L168-L170.	1.5	46
28	Growth Kinetics and Behavior of Dust Particles in Silane Plasmas. Japanese Journal of Applied Physics, 1993, 32, 3074-3080.	1.5	44
29	Improving the performance of quantum dot sensitized solar cells through CdNiS quantum dots with reduced recombination and enhanced electron lifetime. Dalton Transactions, 2016, 45, 8447-8457.	3.3	44
30	Surface Reaction Kinetics of CH ₃ in CH ₄ RF Discharge Studied by Time-Resolved Threshold Ionization Mass Spectrometry. Japanese Journal of Applied Physics, 1997, 36, 4752-4755.	1.5	43
31	Correlation between volume fraction of clusters incorporated into a-Si:H films and hydrogen content associated with Si-H bonds in the films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 1536-1539.	2.1	42
32	Two-dimensional concentration distribution of reactive oxygen species transported through a tissue phantom by atmospheric-pressure plasma-jet irradiation. Applied Physics Express, 2016, 9, 076202.	2.4	41
33	Nano-factories in plasma: present status and outlook. Journal Physics D: Applied Physics, 2011, 44, 174038.	2.8	40
34	Antioxidative activity and growth regulation of Brassicaceae induced by oxygen radical irradiation. Japanese Journal of Applied Physics, 2015, 54, 06GD01.	1.5	40
35	Variation in structure of proteins by adjusting reactive oxygen and nitrogen species generated from dielectric barrier discharge jet. Scientific Reports, 2016, 6, 35883.	3.3	40
36	Roles of SiH ₃ and SiH ₂ Radicals in Particle Growth in rf Silane Plasmas. Japanese Journal of Applied Physics, 1997, 36, 4985-4988.	1.5	39

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37	Effects of gas flow on oxidation reaction in liquid induced by He/O ₂ plasma-jet irradiation. Journal of Applied Physics, 2015, 118, .	2.5	39
38	Plant Growth Enhancement of Seeds Immersed in Plasma Activated Water. MRS Advances, 2017, 2, 995-1000.	0.9	38
39	In situ polarization-sensitive laser-light-scattering method for simultaneous measurements of two-dimensional spatial size and density distributions of particles in plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 603-607.	2.1	36
40	In situ simple method for measuring size and density of nanoparticles in reactive plasmas. Journal of Applied Physics, 2006, 99, 083302.	2.5	36
41	Effects of irradiation distance on supply of reactive oxygen species to the bottom of a Petri dish filled with liquid by an atmospheric O ₂ /He plasma jet. Journal of Applied Physics, 2016, 119, .	2.5	36
42	In Situ Observation of Particle Behavior in rf Silane Plasmas. Japanese Journal of Applied Physics, 1991, 30, 1887-1892.	1.5	35
43	High rate deposition of highly stable a-Si:H films using multi-hollow discharges for thin films solar cells. Surface and Coatings Technology, 2010, 205, S241-S245.	4.8	35
44	Effects of Gas Flow on Particle Growth in Silane RF Discharges. Japanese Journal of Applied Physics, 1999, 38, 4556-4560.	1.5	34
45	Growth of particles in cluster-size range in low pressure and low power SiH ₄ rf discharges. Journal of Applied Physics, 1999, 86, 3543-3549.	2.5	33
46	Development of Photon-Counting Laser-Light-Scattering Method for Detection of Nano-Particles Formed in CVD Plasmas.. The Review of Laser Engineering, 1998, 26, 449-452.	0.0	33
47	Transport of nano-particles in capacitively coupled rf discharges without and with amplitude modulation of discharge voltage. Journal Physics D: Applied Physics, 2007, 40, 2267-2271.	2.8	32
48	Growth Enhancement of Radish Sprouts Induced by Low Pressure O ₂ Radio Frequency Discharge Plasma Irradiation. Japanese Journal of Applied Physics, 2012, 51, 01AE01.	1.5	32
49	Polymer counter electrode of poly(3,4-ethylenedioxythiophene):Poly(4-styrenesulfonate) containing TiO ₂ nano-particles for dye-sensitized solar cells. Journal of Power Sources, 2016, 307, 25-30.	7.8	32
50	Alterations of DNA Methylation Caused by Cold Plasma Treatment Restore Delayed Germination of Heat-Stressed Rice (<i>Oryza sativa</i> L.) Seeds. ACS Agricultural Science and Technology, 2021, 1, 5-10.	2.3	32
51	Analysis on the effect of polysulfide electrolyte composition for higher performance of Si quantum dot-sensitized solar cells. Electrochimica Acta, 2013, 95, 43-47.	5.2	31
52	Sterilization characteristics of the surfaces of agricultural products using active oxygen species generated by atmospheric plasma and UV light. Japanese Journal of Applied Physics, 2014, 53, 05FR03.	1.5	30
53	Visualization of the Distribution of Oxidizing Substances in an Atmospheric Pressure Plasma Jet. IEEE Transactions on Plasma Science, 2014, 42, 2482-2483.	1.3	30
54	Relationship between cold plasma treatment-induced changes in radish seed germination and phytohormone balance. Japanese Journal of Applied Physics, 2020, 59, SH1001.	1.5	30

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55	Study on growth processes of particles in germane radio frequency discharges using laser light scattering and scanning electron microscopic methods. <i>Journal of Applied Physics</i> , 1998, 83, 5665-5669.	2.5	29
56	Production of crystalline Si nano-clusters using pulsed H ₂ +SiH ₄ VHF discharges. <i>Thin Solid Films</i> , 2006, 506-507, 288-291.	1.8	29
57	High quality epitaxial ZnO films grown on solid-phase crystallized buffer layers. <i>Thin Solid Films</i> , 2012, 520, 4674-4677.	1.8	28
58	Dielectric barrier discharge plasma treatment-induced changes in sunflower seed germination, phytohormone balance, and seedling growth. <i>Applied Physics Express</i> , 2019, 12, 126003.	2.4	28
59	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. <i>Scientific Reports</i> , 2021, 11, 2539.	3.3	28
60	Detection of Negative Ions in a Helium-Silane RF Plasma. <i>Japanese Journal of Applied Physics</i> , 1992, 31, L1791-L1793.	1.5	27
61	Characterization of Dust Particles Ranging in Size from 1 nm to 10 Åµm Collected in the LHD. <i>Plasma and Fusion Research</i> , 2009, 4, 034-034.	0.7	26
62	Plasma surface treatment of polymers with inductivity-coupled RF plasmas driven by low-inductance antenna units. <i>Thin Solid Films</i> , 2009, 518, 1006-1011.	1.8	26
63	Surface nitridation of silicon nano-particles using double multi-hollow discharge plasma CVD. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 3017-3020.	0.8	26
64	Rapid transport of nano-particles having a fractional elementary charge on average in capacitively-coupled rf discharges by amplitude-modulating discharge voltage. <i>Faraday Discussions</i> , 2008, 137, 127-138.	3.2	25
65	The changes in particle charge distribution during rapid growth of particles in the plasma reactor. <i>Journal of Colloid and Interface Science</i> , 2003, 257, 195-207.	9.4	24
66	Enhanced light harvesting and charge recombination control with TiO ₂ /PbCdS/CdS based quantum dot-sensitized solar cells. <i>Journal of Electroanalytical Chemistry</i> , 2017, 788, 131-136.	3.8	24
67	Impact of atmospheric pressure plasma treated seeds on germination, morphology, gene expression and biochemical responses. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 040502.	1.5	24
68	Investigation of Particulate Growth Processes in RF Silane Plasmas Using Light Absorption and Scanning Electron Microscopic Methods. <i>Japanese Journal of Applied Physics</i> , 1994, 33, 4198-4201.	1.5	23
69	Nucleation and subsequent growth of clusters in reactive plasmas. <i>Plasma Sources Science and Technology</i> , 2002, 11, A229-A233.	3.1	23
70	Reduced recombination with an optimized barrier layer on TiO ₂ in PbS/CdS core shell quantum dot sensitized solar cells. <i>New Journal of Chemistry</i> , 2016, 40, 3423-3431.	2.8	23
71	Characteristics of crystalline sputtered LaFeO ₃ thin films as photoelectrochemical water splitting photocathodes. <i>Nanoscale</i> , 2020, 12, 9653-9660.	5.6	23
72	Plasma-enhanced metal organic chemical vapor deposition of high purity copper thin films using plasma reactor with the H atom source. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1999, 17, 726-730.	2.1	22

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73	Electron Field Emission from Self-Organized Micro-Emitters of sp ³ -Bonded 5H Boron Nitride with Very High Current Density at Low Electric Field. <i>Journal of Physical Chemistry B</i> , 2004, 108, 5182-5184.	2.6	22
74	X-Ray photoelectron spectroscopy analysis of plasma-polymer interactions for development of low-damage plasma processing of soft materials. <i>Thin Solid Films</i> , 2010, 518, 6492-6495.	1.8	22
75	Plasma interactions with amino acid (L-alanine) as a basis of fundamental processes in plasma medicine. <i>Current Applied Physics</i> , 2013, 13, S59-S63.	2.4	22
76	Formation Kinetics and Control of Dust Particles in Capacitively-Coupled Reactive Plasmas. <i>Physica Scripta</i> , 2001, T89, 29.	2.5	21
77	Cluster-eliminating filter for depositing cluster-free a-Si:H films by plasma chemical vapor deposition. <i>Review of Scientific Instruments</i> , 2005, 76, 113501.	1.3	21
78	Impacts of Amplitude Modulation of RF Discharge Voltage on the Growth of Nanoparticles in Reactive Plasmas. <i>Applied Physics Express</i> , 2011, 4, 105001.	2.4	21
79	Growth of single crystalline films on lattice-mismatched substrates through 3D to 2D mode transition. <i>Scientific Reports</i> , 2020, 10, 4669.	3.3	21
80	Plasma treatment causes structural modifications in lysozyme, and increases cytotoxicity towards cancer cells. <i>International Journal of Biological Macromolecules</i> , 2021, 182, 1724-1736.	7.5	21
81	A study on the time evolution of surface loss probability on hydrogenated amorphous silicon films in rf discharges using infrared diode-laser absorption spectroscopy. <i>Journal Physics D: Applied Physics</i> , 1998, 31, 776-780.	2.8	20
82	H-assisted plasma CVD of Cu films for interconnects in ultra-large-scale integration. <i>Science and Technology of Advanced Materials</i> , 2001, 2, 505-515.	6.1	20
83	Highly crystalline 5H-polytype of sp ³ -bonded boron nitride prepared by plasma-packets-assisted pulsed-laser deposition: An ultraviolet light emitter at 225 nm. <i>Applied Physics Letters</i> , 2002, 81, 4547-4549.	3.3	20
84	Cluster-suppressed plasma CVD for deposition of high quality a-Si:H films. <i>Thin Solid Films</i> , 2003, 427, 1-5.	1.8	20
85	Mechanism of Cu deposition from Cu(EDMD)2 using H-assisted plasma CVD. <i>Thin Solid Films</i> , 2006, 506-507, 197-201.	1.8	20
86	Etching characteristics of organic low-k films interpreted by internal parameters employing a combinatorial plasma process in an inductively coupled H ₂ /N ₂ plasma. <i>Journal of Applied Physics</i> , 2010, 107, .	2.5	20
87	Cold Plasma Treatment of Sunflower Seeds Modulates Plant-Associated Microbiome and Stimulates Root and Lateral Organ Growth. <i>Frontiers in Plant Science</i> , 2020, 11, 568924.	3.6	20
88	Impact of radish sprouts seeds coat color on the electron paramagnetic resonance signals after plasma treatment. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SHHF01.	1.5	20
89	The protective action of osmolytes on the deleterious effects of gamma rays and atmospheric pressure plasma on protein conformational changes. <i>Scientific Reports</i> , 2017, 7, 8698.	3.3	19
90	Impact of an ionic liquid on protein thermodynamics in the presence of cold atmospheric plasma and gamma rays. <i>Physical Chemistry Chemical Physics</i> , 2017, 19, 25277-25288.	2.8	19

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91	Structural modification of NADPH oxidase activator (Noxa 1) by oxidative stress: An experimental and computational study. <i>International Journal of Biological Macromolecules</i> , 2020, 163, 2405-2414.	7.5	19
92	Nanoparticle coagulation in fractionally charged and charge fluctuating dusty plasmas. <i>Physics of Plasmas</i> , 2008, 15, .	1.9	18
93	Effects of photoirradiation in UV and VUV regions during plasma exposure to polymers. <i>Thin Solid Films</i> , 2011, 519, 6810-6814.	1.8	18
94	The blocking effect of charge recombination by sputtered and acid-treated ZnO thin film in dye-sensitized solar cells. <i>Journal of Photochemistry and Photobiology A: Chemistry</i> , 2012, 248, 50-54.	3.9	18
95	The reduction of charge recombination and performance enhancement by the surface modification of Si quantum dot-sensitized solar cell. <i>Electrochimica Acta</i> , 2013, 87, 213-217.	5.2	18
96	Effect of Nitridation of Si Nanoparticles on the Performance of Quantum-Dot Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AD01.	1.5	18
97	Species responsible for Si-H bond formation in a-Si:H films deposited using silane high frequency discharges. <i>Thin Solid Films</i> , 2006, 506-507, 17-21.	1.8	17
98	Surface loss probabilities of H and N radicals on different materials in afterglow plasmas employing H ₂ and N ₂ mixture gases. <i>Journal of Applied Physics</i> , 2010, 107, 103310.	2.5	17
99	Local supply of reactive oxygen species into a tissue model by atmospheric-pressure plasma-jet exposure. <i>Journal of Applied Physics</i> , 2019, 125, 213303.	2.5	17
100	Transition of Particle Growth Region in SiH ₄ RF Discharges. <i>Japanese Journal of Applied Physics</i> , 1998, 37, 5757-5762.	1.5	16
101	Control of deposition profile of Cu for large-scale integration (LSI) interconnects by plasma chemical vapor deposition. <i>Pure and Applied Chemistry</i> , 2005, 77, 391-398.	1.9	16
102	X-ray photoelectron spectroscopy for analysis of plasma-polymer interactions in Ar plasmas sustained via RF inductive coupling with low-inductance antenna units. <i>Thin Solid Films</i> , 2010, 518, 3555-3560.	1.8	16
103	Transport control of dust particles via the electrical asymmetry effect: experiment, simulation and modelling. <i>Journal Physics D: Applied Physics</i> , 2013, 46, 245202.	2.8	16
104	Epitaxial Growth of ZnInON Films with Tunable Band Gap from 1.7 to 3.3 eV on ZnO Templates. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 11NM06.	1.5	16
105	Low temperature synthesis of silicon quantum dots with plasma chemistry control in dual frequency non-thermal plasmas. <i>Physical Chemistry Chemical Physics</i> , 2016, 18, 15697-15710.	2.8	16
106	Study on Growth Processes of Subnanometer Particles in Early Phase of Silane RF Discharge. <i>Japanese Journal of Applied Physics</i> , 1994, 33, 4212-4215.	1.5	15
107	Conformal Deposition of High-Purity Copper Using Plasma Reactor with H Atom Source. <i>Japanese Journal of Applied Physics</i> , 1999, 38, 4492-4495.	1.5	15
108	Combinatorial Plasma Etching Process. <i>Applied Physics Express</i> , 2009, 2, 096001.	2.4	15

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109	Fabrication of ZnInON/ZnO multi-quantum well solar cells. <i>Thin Solid Films</i> , 2015, 587, 106-111.	1.8	15
110	DNA Microarray Analysis of Plant Seeds Irradiated by Active Oxygen Species in Oxygen Plasma. <i>Plasma Medicine</i> , 2016, 6, 459-471.	0.6	15
111	Low-damage surface modification of polymethylmethacrylate with argon-oxygen mixture plasmas driven by multiple low-inductance antenna units. <i>Thin Solid Films</i> , 2010, 518, 3561-3565.	1.8	14
112	Plasma processing of soft materials for development of flexible devices. <i>Thin Solid Films</i> , 2011, 519, 6721-6726.	1.8	14
113	Effects of Nitrogen on Crystal Growth of Sputter-Deposited ZnO Films for Transparent Conducting Oxide. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 11NB03.	1.5	14
114	Size and flux of carbon nanoparticles synthesized by Ar+CH ₄ multi-hollow plasma chemical vapor deposition. <i>Diamond and Related Materials</i> , 2020, 109, 108050.	3.9	14
115	Subacute Pulmonary Toxicity of Copper Indium Gallium Diselenide Following Intratracheal Instillations into the Lungs of Rats. <i>Journal of Occupational Health</i> , 2012, 54, 187-195.	2.1	13
116	Growth Control of Dry Yeast Using Scalable Atmospheric-Pressure Dielectric Barrier Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 11PJ02.	1.5	13
117	Gas Flow Rate Dependence of the Discharge Characteristics of a Plasma Jet Impinging Onto the Liquid Surface. <i>IEEE Transactions on Plasma Science</i> , 2015, 43, 4081-4087.	1.3	13
118	Effect of sulfur doped TiO ₂ on photovoltaic properties of dye-sensitized solar cells. <i>Electronic Materials Letters</i> , 2016, 12, 530-536.	2.2	13
119	Cold plasma treatment of <i>Arabidopsis thaliana</i> (L.) seeds modulates plant-associated microbiome composition. <i>Applied Physics Express</i> , 2020, 13, 076001.	2.4	13
120	Influence of osmolytes and ionic liquids on the Bacteriorhodopsin structure in the absence and presence of oxidative stress: A combined experimental and computational study. <i>International Journal of Biological Macromolecules</i> , 2020, 148, 657-665.	7.5	13
121	Possible impact of plasma oxidation on the structure of the C-terminal domain of SARS-CoV-2 spike protein: a computational study. <i>Applied Physics Express</i> , 2021, 14, 027002.	2.4	13
122	Diagnostics of plasma for metal - organic chemical vapour deposition of Cu and fabrication of Cu thin films using the plasma. <i>Journal Physics D: Applied Physics</i> , 1996, 29, 2754-2758.	2.8	12
123	Electron field emission in air at an atmospheric pressure from sp ³ -bonded 5H-BN microcones. <i>Journal of Applied Physics</i> , 2007, 101, 084904.	2.5	12
124	Discharge power dependence of H α intensity and electron density of Ar+H ₂ discharges in H-assisted plasma CVD reactor. <i>Surface and Coatings Technology</i> , 2008, 202, 5659-5662.	4.8	12
125	Two-Dimensional Spatial Profile of Volume Fraction of Nanoparticles Incorporated Into a-Si:H Films Deposited by Plasma CVD. <i>IEEE Transactions on Plasma Science</i> , 2008, 36, 888-889.	1.3	12
126	Combinatorial analyses of plasma-polymer interactions. <i>Surface and Coatings Technology</i> , 2011, 205, S484-S489.	4.8	12

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127	Redox Characteristics of Thiol Compounds Using Radicals Produced by Water Vapor Radio Frequency Discharge. Japanese Journal of Applied Physics, 2011, 50, 08JF04.	1.5	12
128	High Amount Cluster Incorporation in Initial Si Film Deposition by SiH ₄ Plasma Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2013, 52, 01AD01.	1.5	12
129	Improvement of Si Adhesion and Reduction of Electron Recombination for Si Quantum Dot-Sensitized Solar Cells. Japanese Journal of Applied Physics, 2013, 52, 01AD05.	1.5	12
130	Surface Modification of Polymer Counter Electrode for Low Cost Dye-sensitized Solar Cells. Electrochimica Acta, 2016, 210, 880-887.	5.2	12
131	Synthesis of Yb ³⁺ /Ho ³⁺ co-doped Y ₂ O ₃ nanoparticles and its application to dye sensitized solar cells. Journal of Molecular Structure, 2021, 1228, 129479.	3.6	12
132	Outcomes of Pulsed Electric Fields and Nonthermal Plasma Treatments on Seed Germination and Protein Functions. Agronomy, 2022, 12, 482.	3.0	12
133	Anisotropic deposition of Cu in trenches by H-assisted plasma chemical vapor deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 1903-1907.	2.1	11
134	Low-damage plasma processing of polymers for development of organic-inorganic flexible devices. Surface and Coatings Technology, 2010, 205, S355-S359.	4.8	11
135	Quantum dot-sensitized solar cells using Si nanoparticles. Transactions of the Materials Research Society of Japan, 2010, 35, 597-599.	0.2	11
136	Improvement on the Electron Transfer of Dye-Sensitized Solar Cell Using Vanadium Doped TiO ₂ . Japanese Journal of Applied Physics, 2013, 52, 11NM02.	1.5	11
137	Densities and Surface Reaction Probabilities of Oxygen and Nitrogen Atoms During Sputter Deposition of ZnInON on ZnO. IEEE Transactions on Plasma Science, 2017, 45, 323-327.	1.3	11
138	Progress in photovoltaic performance of organic/inorganic hybrid solar cell based on optimal resistive Si and solvent modified poly(3,4-ethylenedioxythiophene) poly(styrenesulfonate) junction. Progress in Photovoltaics: Research and Applications, 2018, 26, 145-150.	8.1	11
139	Long-term response of Norway spruce to seed treatment with cold plasma: Dependence of the effects on the genotype. Plasma Processes and Polymers, 2021, 18, 2000159.	3.0	11
140	Treatment of organic wastewater by a combination of non-thermal plasma and catalyst: a review. Reviews of Modern Plasma Physics, 2022, 6, .	4.1	11
141	Anisotropic deposition of copper by H-assisted plasma chemical vapor deposition. Materials Science in Semiconductor Processing, 2002, 5, 301-304.	4.0	10
142	Characteristics of photocurrent generation in the near-ultraviolet region in Si quantum-dot sensitized solar cells. Thin Solid Films, 2013, 544, 93-98.	1.8	10
143	Dust particle formation due to interaction between graphite and helicon deuterium plasmas. Fusion Engineering and Design, 2013, 88, 28-32.	1.9	10
144	Off-axis sputter deposition of ZnO films on c-sapphire substrates by utilizing nitrogen-mediated crystallization method. Optical Engineering, 2014, 53, 087109.	1.0	10

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145	Effects of cluster incorporation into hydrogenated amorphous silicon films in initial discharge phase on film stability. <i>Thin Solid Films</i> , 2015, 587, 126-131.	1.8	10
146	Improved Nanoscale Al-Doped ZnO with a ZnO Buffer Layer Fabricated by Nitrogen-Mediated Crystallization for Flexible Optoelectronic Devices. <i>ACS Applied Nano Materials</i> , 2020, 3, 2480-2490.	5.0	10
147	Redox Characteristics of Thiol Compounds Using Radicals Produced by Water Vapor Radio Frequency Discharge. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 08JF04.	1.5	10
148	Condensation of sp ³ -Bonded Boron Nitride through a Highly Nonequilibrium Fluid State. <i>Journal of Physical Chemistry B</i> , 2004, 108, 205-211.	2.6	9
149	Fractal growth of sp ³ -bonded 5H-BN microcones by plasma-assisted laser chemical vapor deposition. <i>Journal of Applied Physics</i> , 2006, 99, 123512.	2.5	9
150	Mass density control of carbon films deposited by H-assisted plasma CVD method. <i>Surface and Coatings Technology</i> , 2013, 228, S15-S18.	4.8	9
151	Effects of Hydrogen Dilution on ZnO Thin Films Fabricated via Nitrogen-Mediated Crystallization. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 01AC08.	1.5	9
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